

FABRICATION AND CHARACTERIZATION OF RESISTIVE SWITCHING TITANIUM DIOXIDE MEMRISTOR

*A thesis submitted in partial fulfillment of the requirements for the award of degree of **MASTER OF SCIENCE** in **PHYSICS***

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Under the Guidance of

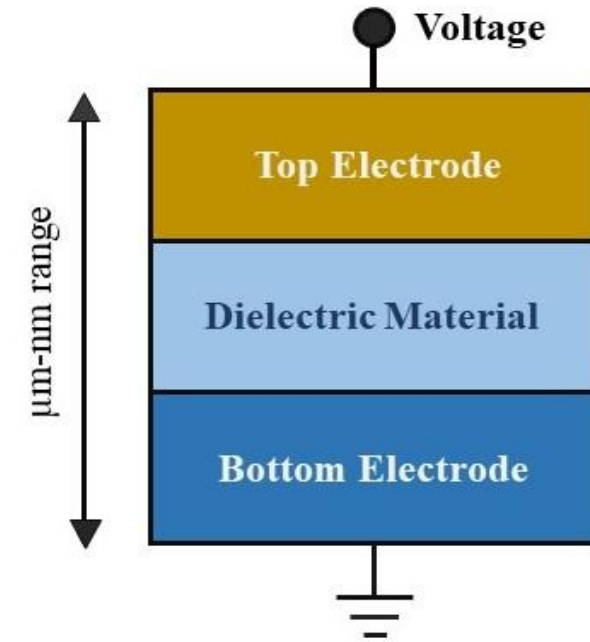
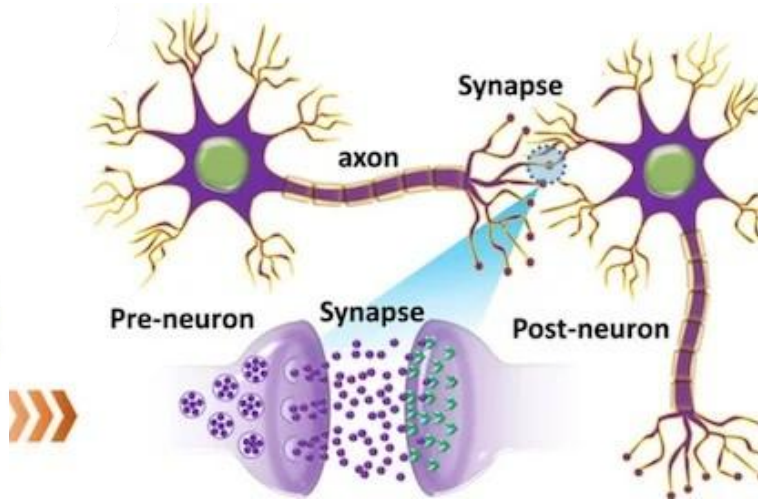
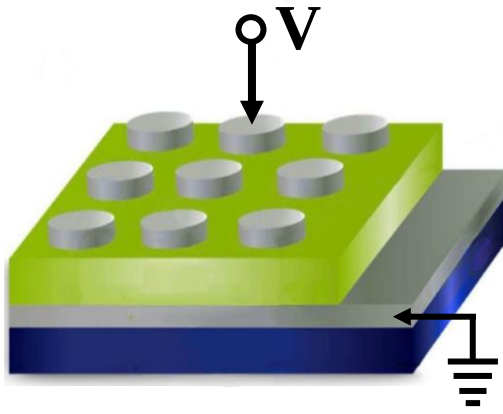
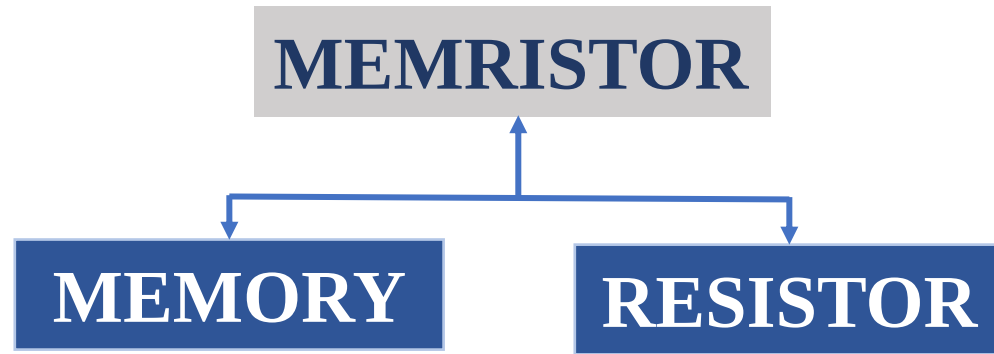
Dr. ALDRIN ANTONY

Associate professor, Department of Physics, CUSAT



June 2025

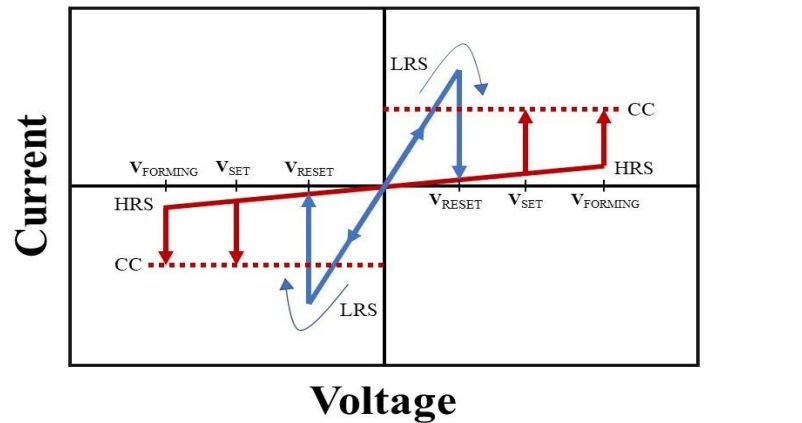
Introduction to Memristors



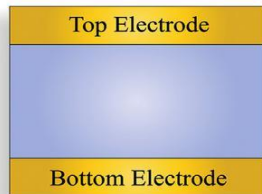
- **Non-Volatile memory device**
- **Neuromorphic computing**
- **MIM Structure**

Resistive Switching

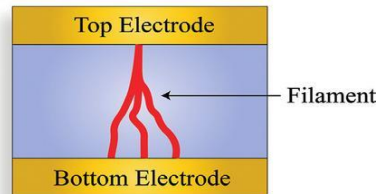
Unipolar Resistive Switching



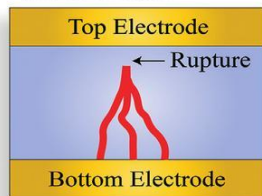
(A) Initial State (as-prepared)



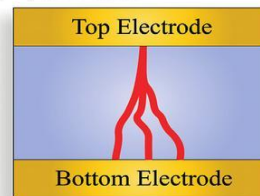
(B) Forming



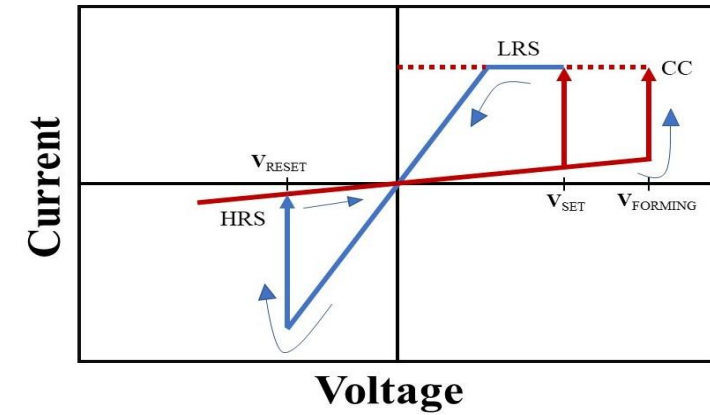
(C) RESET State



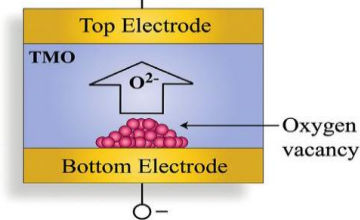
(D) SET State



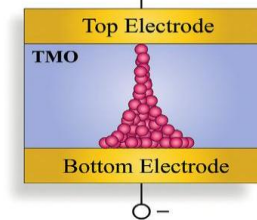
Bipolar Resistive Switching



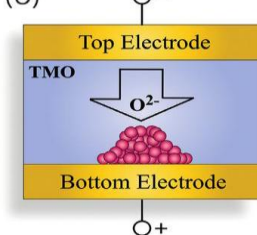
(A)



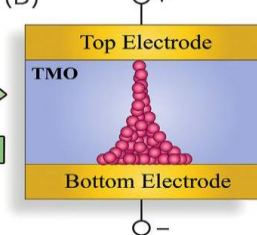
(B)



(C)

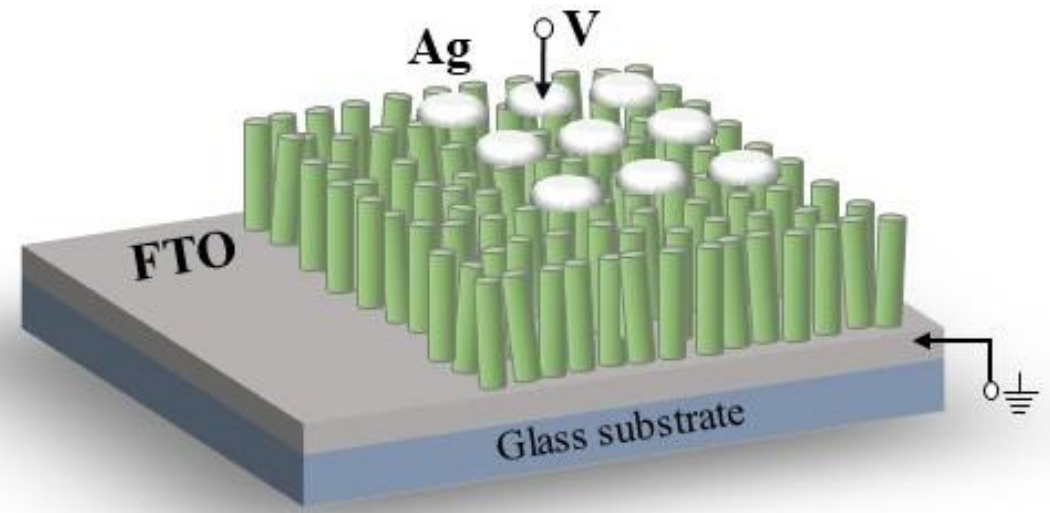


(D)



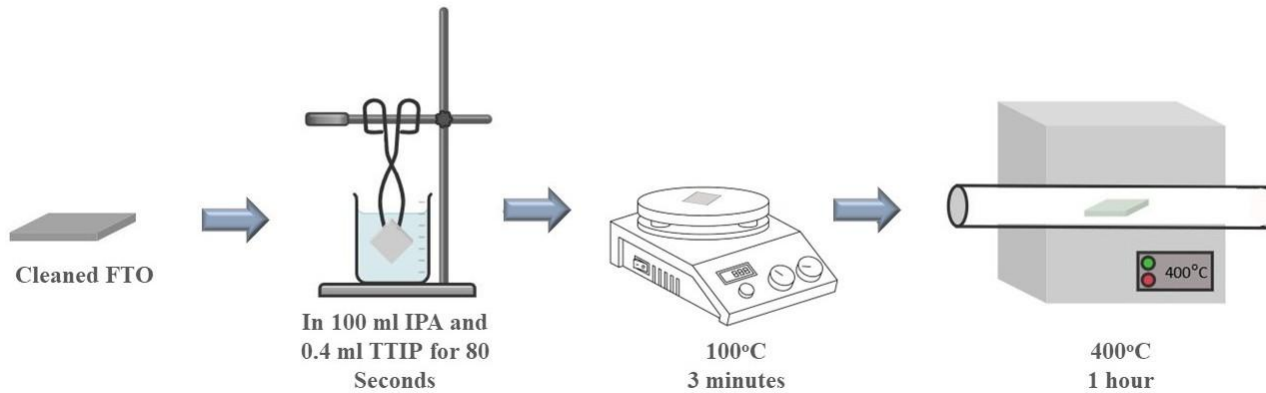
Objective of the Study

- Synthesize TiO_2 nanorods on FTO substrate using seed assisted hydrothermal method.
- Optimization of Hydrothermal growth conditions to suppress unwanted flower-like structures and achieve a clean nanorod morphology.
- Prevention of Silver electrode infiltration between the nanorod using PMMA.
- Fabricate memristor device.
- Characterize material and device properties.



Experimental details

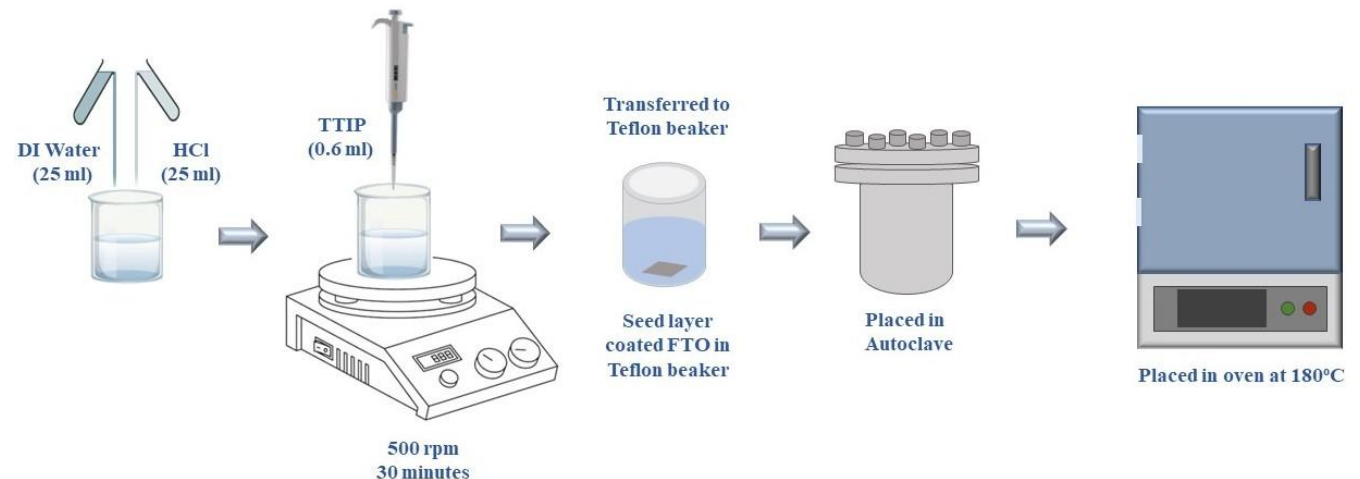
Seed layer Synthesis



- FTO ultrasonicated in Ethanol and DI water
- Dip coating for 80 seconds in 0.4ml TTIP and 100 ml IPA
- Dried in hotplate for 3 minutes at 100°C
- Annealed for 1 hour at 400°C

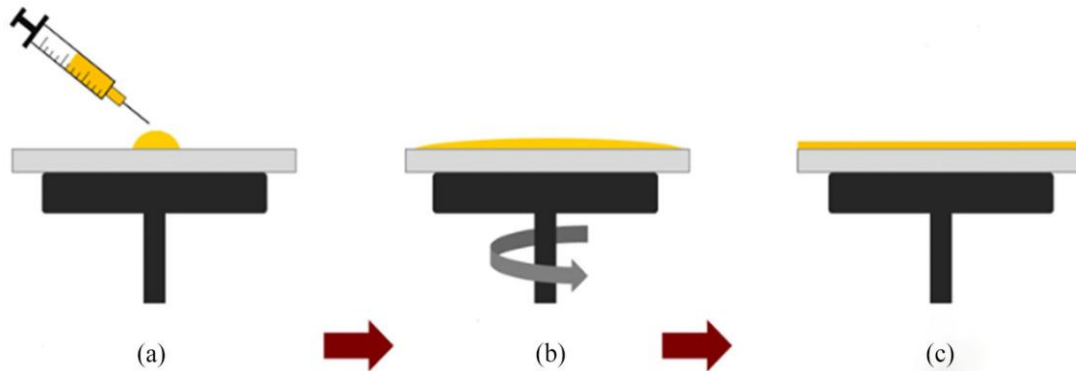
Hydrothermal Synthesis of TiO₂ nanorods

- Stirred 25 ml HCl , 25 ml DI water and 0.6 ml TTIP for 30 minutes
- Transferred to Teflon beaker where seed layer coated FTO is placed
- Placed in an Autoclave
- Placed in Oven at 180°C



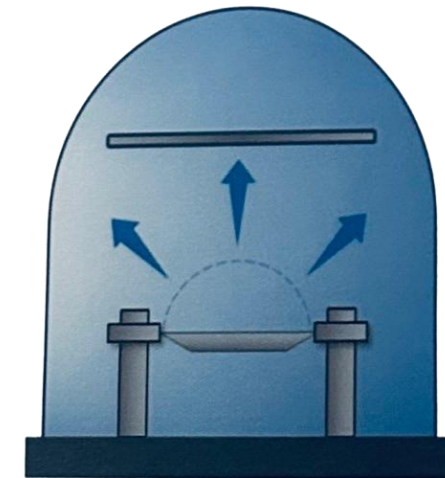
Spin coating with PMMA solution

- To fill the gap between the nanorods.
- PMMA solution of 3 wt% was prepared by dissolving 61.86 mg of PMMA (Alpha Aesar) in 2 ml of Anisole (Sigma-Aldrich, 99%).
- The mixture was stirred at 75°C at 1000 rpm for 1 hour and 20 minutes.
- Spin coated at 4000 rpm for 45 seconds
- Dried at 180°C for 3 minutes in hotplate
- Coated in one-layer and two-layer.



Top electrode deposition by thermal evaporation

- Base pressure : $\sim 7 \times 10^{-6}$
- Source Current : 101 A
- Silver used : ~ 180 mg
- Thickness Achieved : ~ 150 nm
- Thickness measurement done using Stylus profilometer.



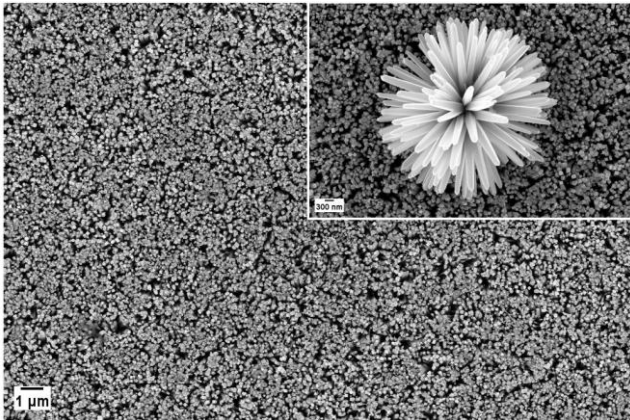
Results and Discussion

Characterization of TiO₂ nanorods

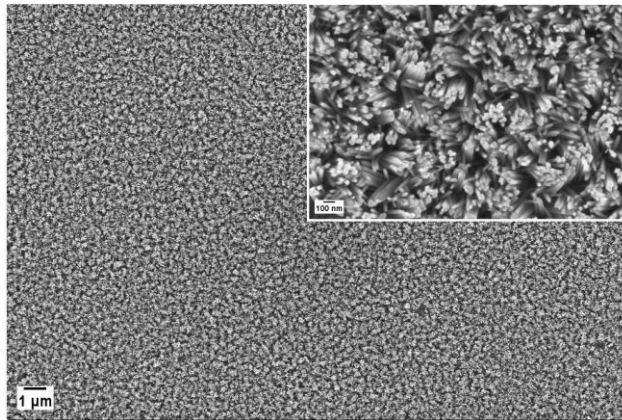
(a) Morphology

Rapid cooled samples

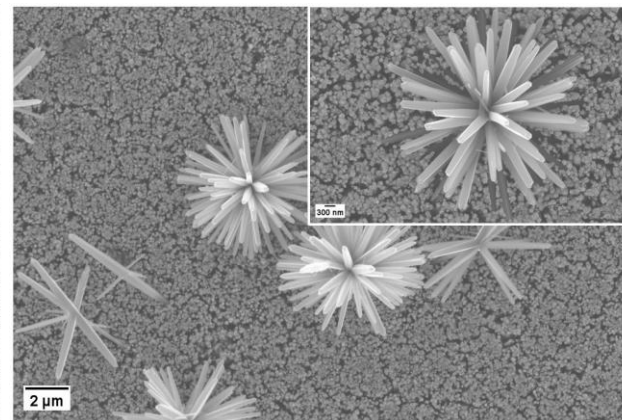
Slow cooled samples



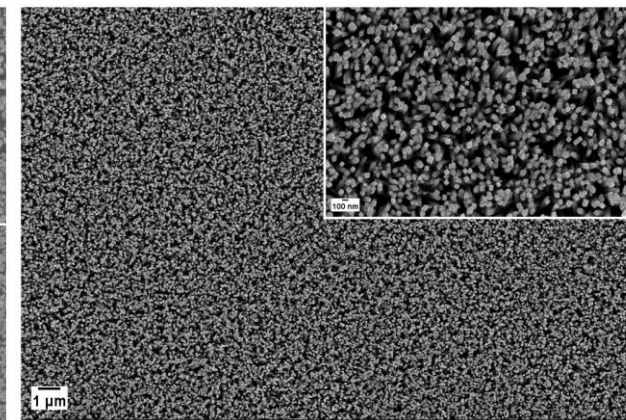
S₃* sample



S₁* sample



S₃ sample

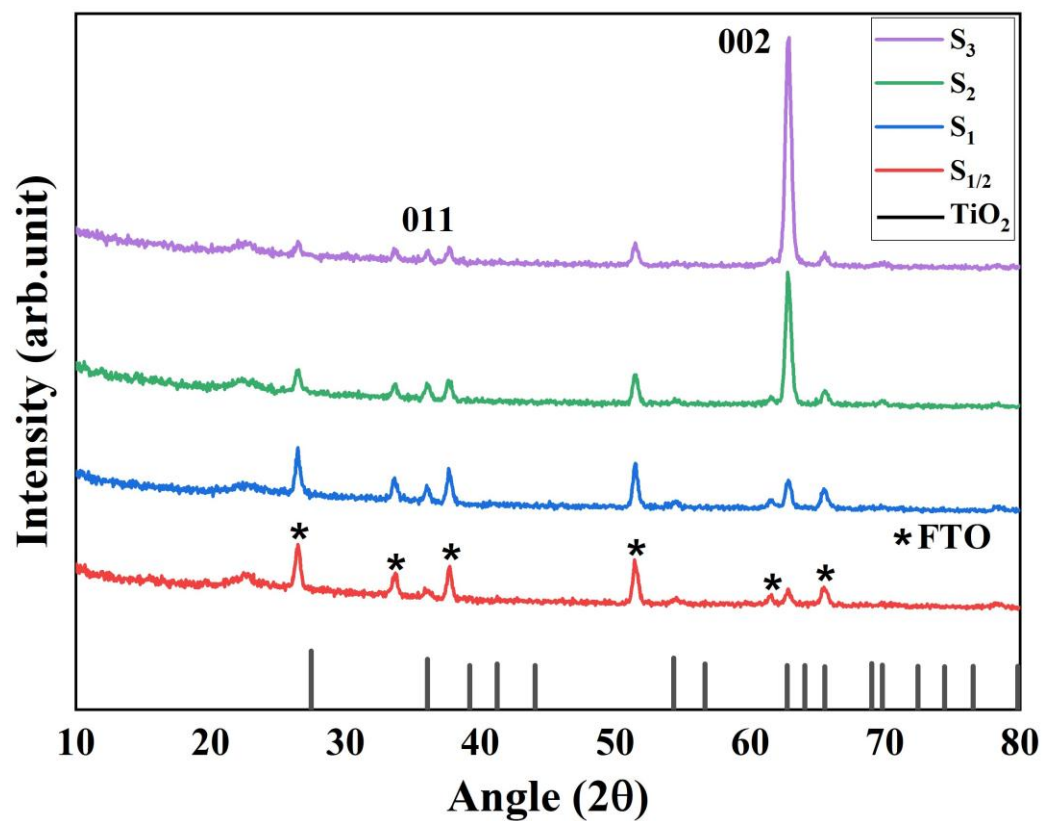


S₁ sample

S ₃ *	S ₂ *	S ₁ *	S ₃	S ₂	S ₁	S _{1/2}
3 hours	2 hours	1 hour	3 hours	2 hours	1 hour	1/2 hour
Rapid cooled	Rapid cooled	Rapid cooled	Slow cooled	Slow cooled	Slow cooled	Slow cooled

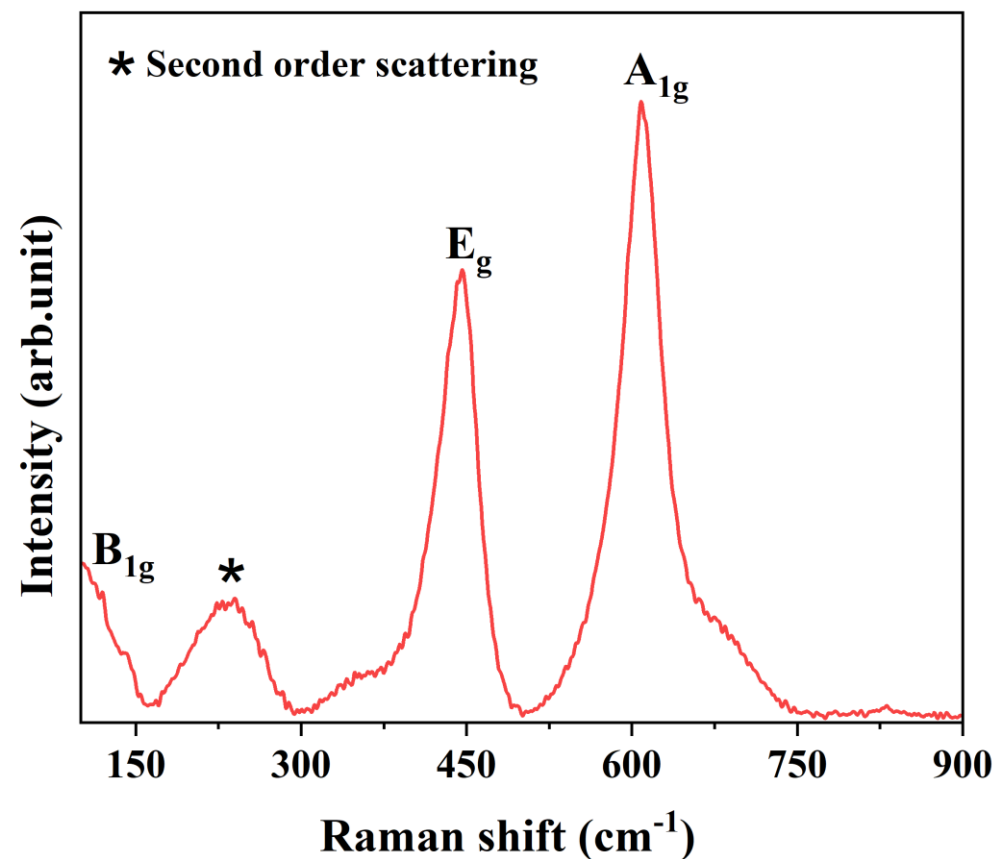
(b) X-Ray Diffraction

- Rutile TiO_2
- $2\theta = 62.7^\circ$ – (002) plane
- $2\theta = 36.1^\circ$ – (011) plane



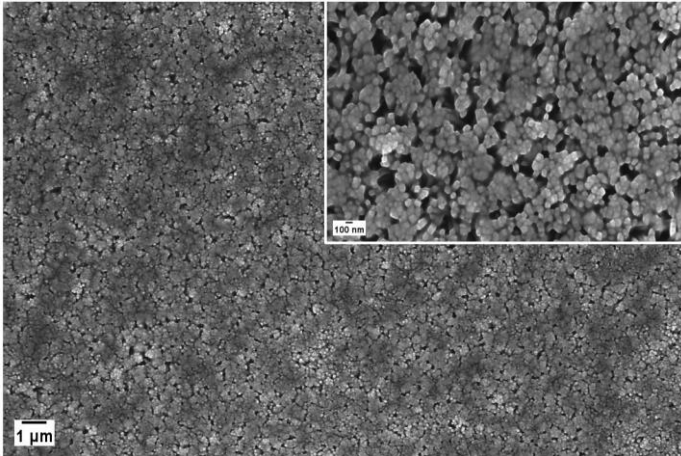
(c) Raman Spectroscopy

- 144 cm^{-1} B_{1g} mode,
- 446 cm^{-1} E_g mode,
- 610 cm^{-1} A_{1g} mode.



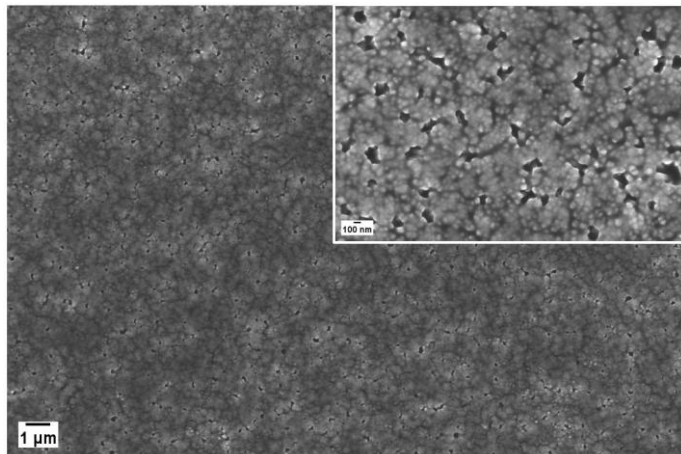
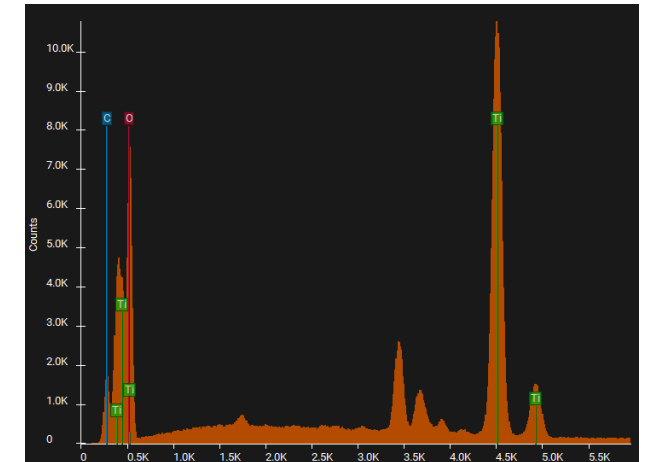
Characterization of PMMA coated TiO₂ nanorods

(a) Morphological and Elemental Analysis



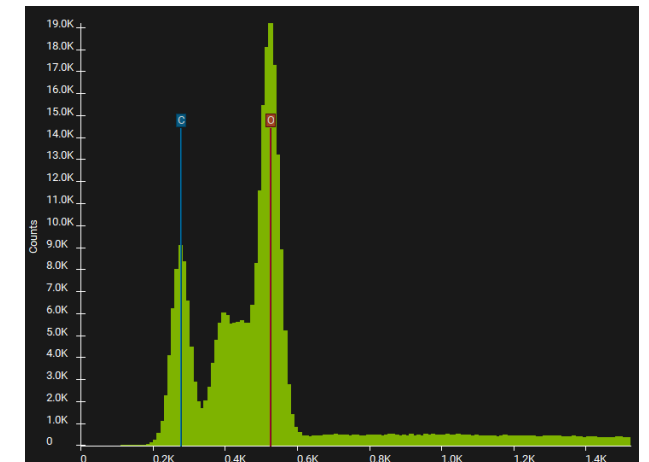
PMMA Coated in one layer

Element	Atomic %	Weight %
Titanium	26.71%	53.56%
Oxygen	57.18%	38.33%
Carbon	16.11%	8.11%

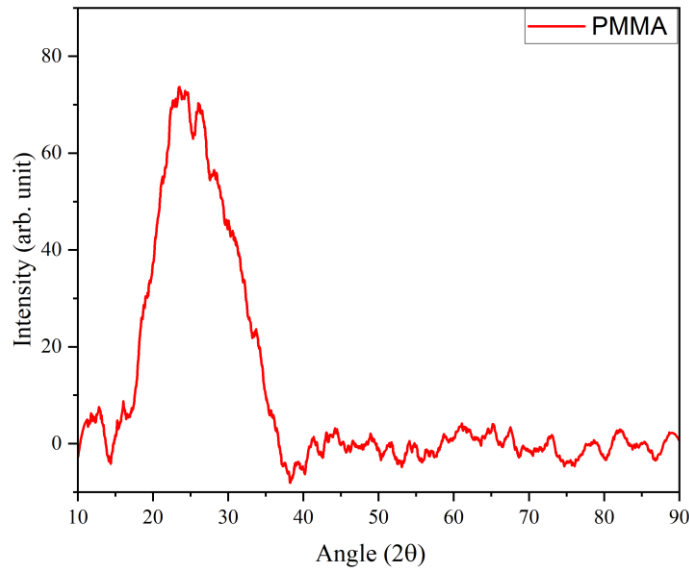


PMMA Coated in two layer

Element	Atomic %	Weight %
Carbon	57.75%	50.64%
Oxygen	42.25%	49.36%

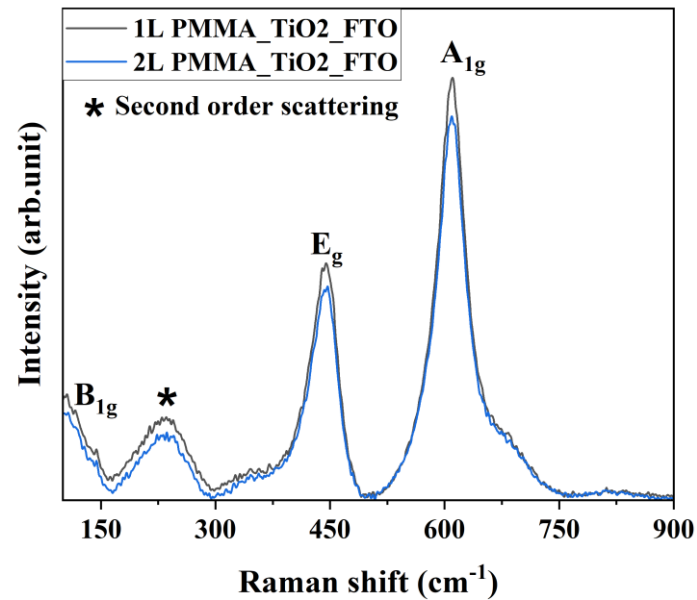


(b) XRD



- Broad humps - Non-crystalline nature
- Reduction in Raman peak intensity – Increased thickness of PMMA layer

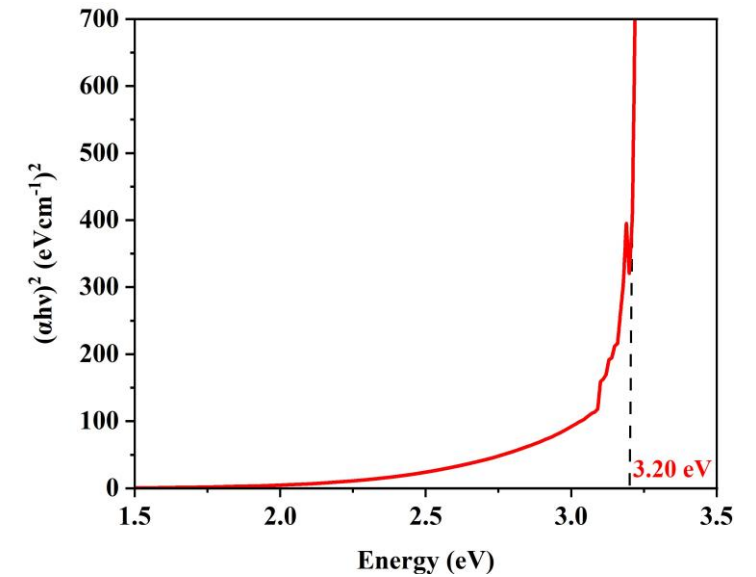
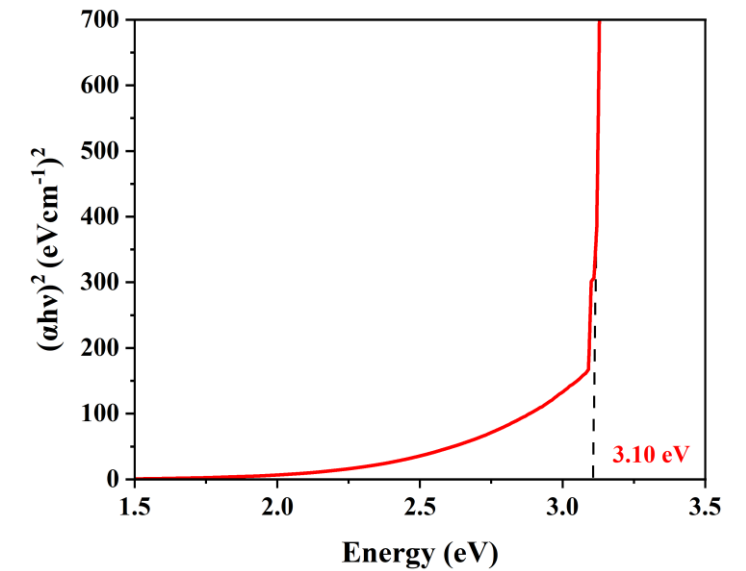
(c) Raman Spectroscopy



- TiO₂ (rutile) – 3.0 eV
1L PMMA_TiO₂ – 3.1 eV
2L PMMA_TiO₂ – 3.2 eV

- Band gap widening – Increased thickness of PMMA layer

(b) UV-Vis Spectroscopy



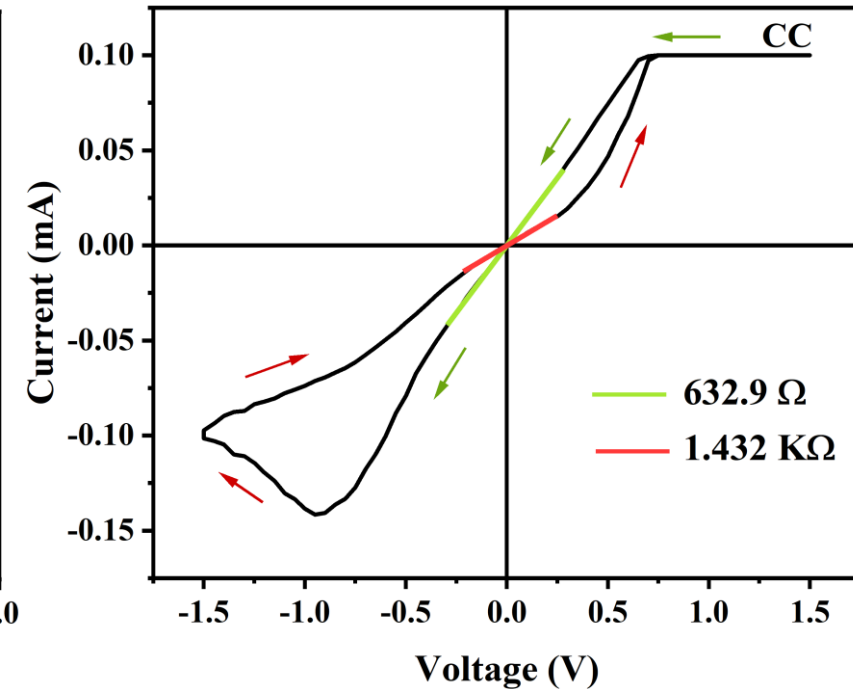
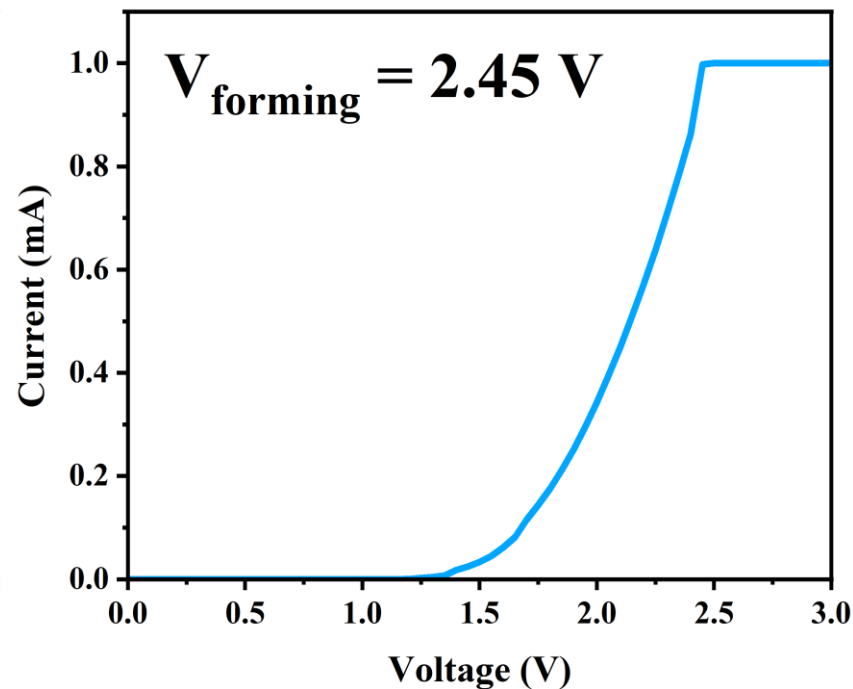
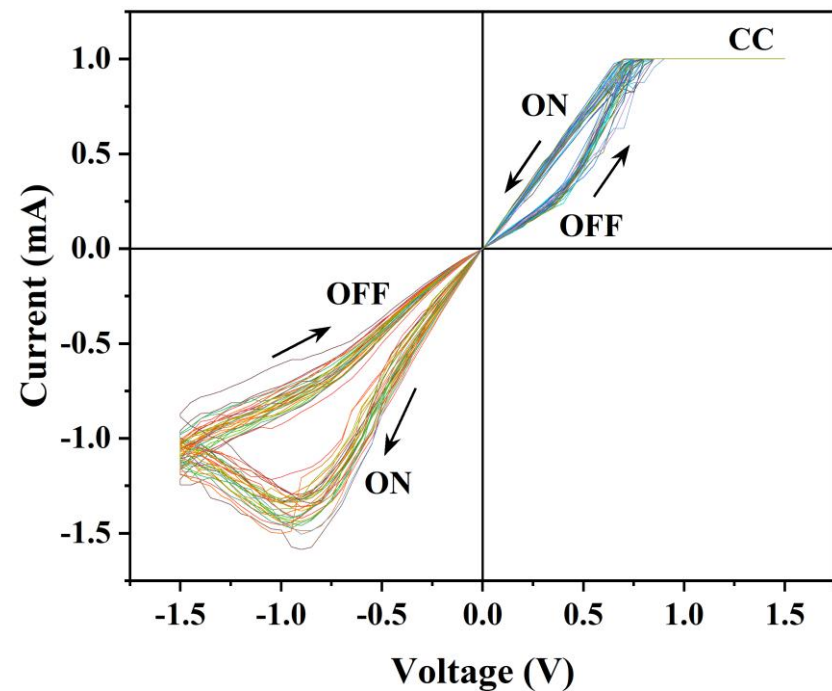
Electrical Characterization

I-V Characteristics

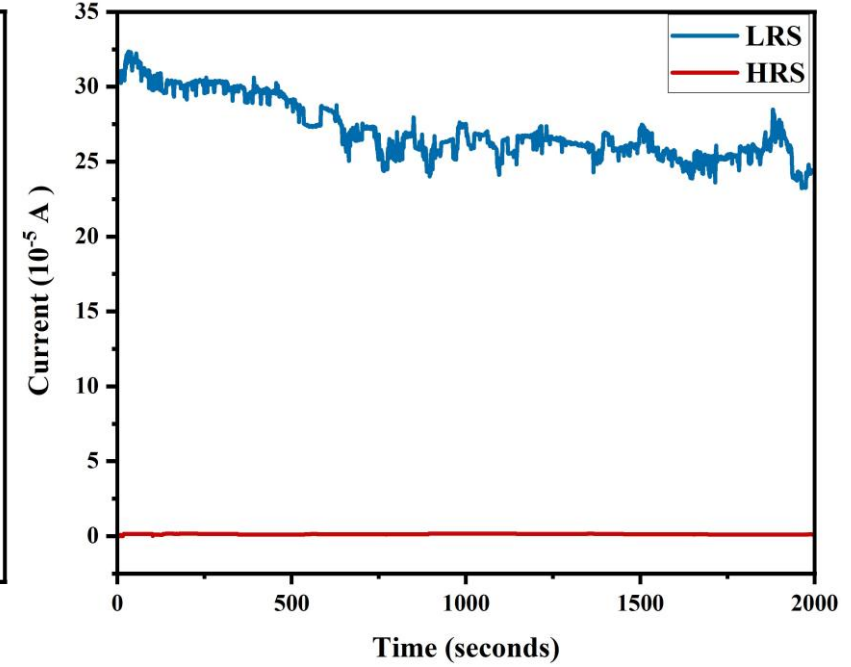
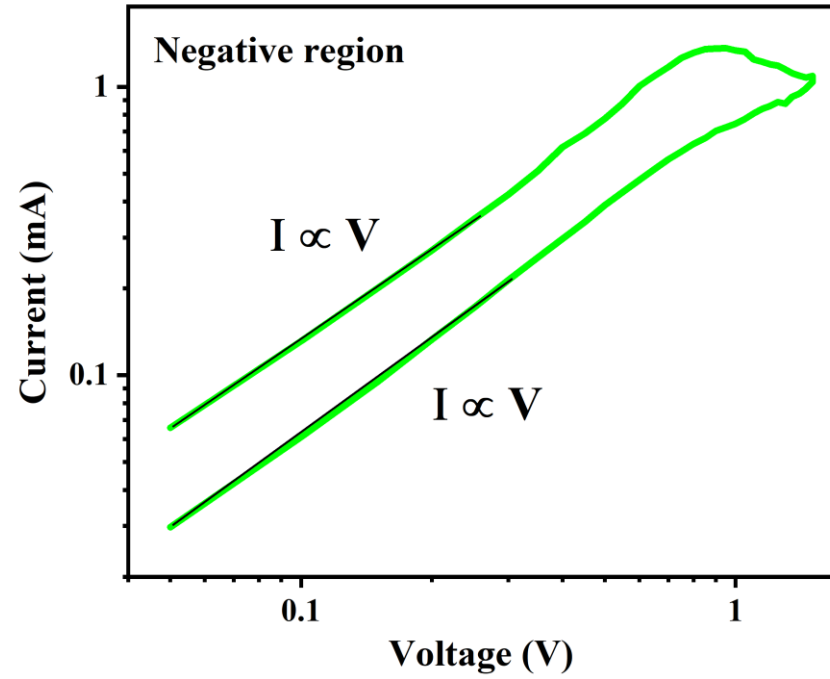
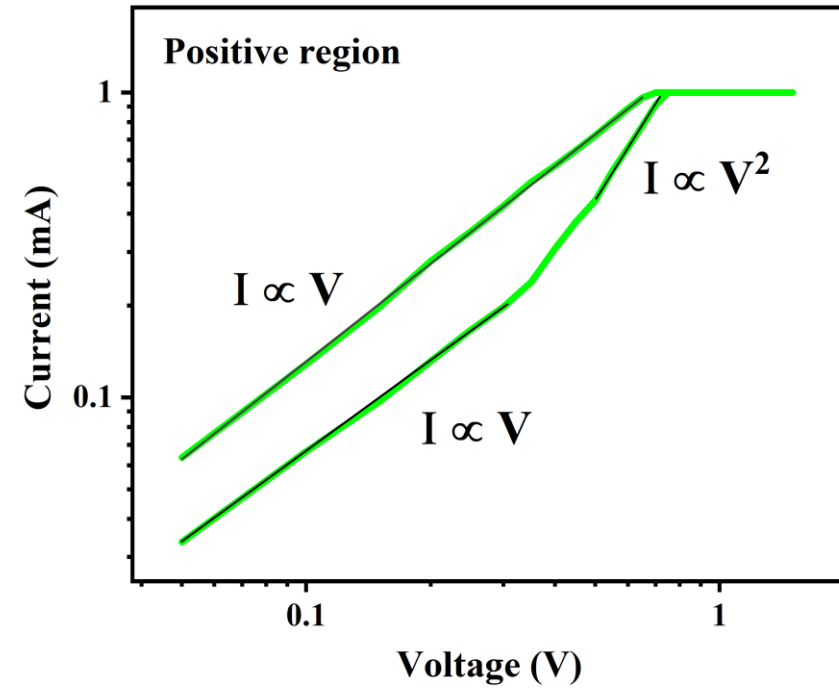
- Forming Voltage : 2.45 V
- V_{set} : 0.4 V
- V_{reset} : -0.9 V
- Endurance : 105 cycles

ON-OFF Ratio

- $R_{\text{OFF}} = 1.432 \text{ K}\Omega$
- $R_{\text{ON}} = 632.9 \Omega$
- ON/OFF Ratio = $R_{\text{OFF}}/R_{\text{ON}}$
= $1.432 \text{ K}\Omega / 632.9 \Omega$
= 2.232



Conduction Mechanism



Conclusion

- **TiO₂-based memristor successfully fabricated using hydrothermal method.**
- **PMMA layer used to prevent Ag infiltration between nanorods.**
- **XRD and Raman spectroscopy confirmed rutile phase; FESEM showed nanorod morphology.**
- **UV-Visible was used spectroscopy to find band gap.**
- **Device showed clear bipolar resistive switching (SET ~0.4 V, RESET ~ -0.9 V).**
- **The device shows an endurance of 10⁵ cycles, a retention time of 2000s and an ON/OFF ratio of 2.232.**

Future work

- **Explore the memristor's potential for neuromorphic computing:**
 - Mimicking synaptic functions like potentiation and depression.
- **Investigate photoresponse under UV illumination:**
 - Analyze I–V characteristics under varying light intensities.
 - Evaluate response time, photocurrent generation, and stability.

Thank you

Presented by
Fathima Shamsad C P